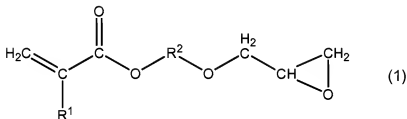


Amendments to the Claims

This is a complete listing of claims and supersedes all other listings:

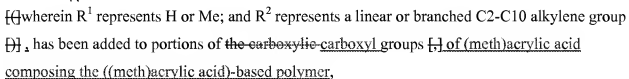
1. (Currently amended) A photosensitive resin composition comprising
 a poly((meth)acrylic acid)-based water-soluble photo-sensitive resin (A) having an acid value of 170 mgKOH/g or more on a solid basis;
 the resin (A) being formed of a ((meth)acrylic acid)-based polymer in which a compound represented by formula (1):



wherein R¹ represents H or Me; and R² represents a linear or branched C2-C10 alkylene group, has been added to portions of the carboxylic-carboxyl groups of (meth)acrylic acid composing the ((meth)acrylic acid)-based polymer,

- a photopolymerization initiator (B); and
 water (C).
2. (Original) A photosensitive resin composition according to claim 1, wherein the carboxyl groups of the ((meth)acrylic acid)-based polymer to which the compound represented by formula (1) has not been added are at least partially neutralized with an alkali.
3. (Currently amended) A method for forming a hydrogel characterized by comprising subjecting a the photosensitive resin composition as recited in claim 1 to photopolymerization.
4. (Currently amended) A hydrogel produced by causing subjecting a photosensitive resin composition to photopolymerize photopolymerization, the photosensitive resin composition comprising

the resin (A) being formed of a ((meth)acrylic acid)-based polymer in which a compound represented by formula (1):



water (C).

5. (Previously presented) A hydrogel according to claim 4, wherein the carboxyl groups of the ((meth)acrylic acid)-based polymer to which the compound represented by formula (1) has not been added are at least partially neutralized with alkali.